

Amendment AF Transmittal

TOWNSEND and TOWNSEND and CREW LLP

(650) 326-2400

In re application of: KARL LITTAU et al.

Application No.: 08/893,917

Filed: July 11, 1997 Group Art Unit: 1763

For: REMOTE PLASMA CLEANING SOURCE HAVING REDUCED REACTIVITY WITH A SUBSTRATE

PROCESSING CHAMBER

Attorney Docket No. ___ AM2119/T21300 16301M-021300US TTC Ref No.

I hereby certify that this is being deposited with the United States Postal Service as first class mail in an envelope addressed to:

Assistant Commissioner for Patents

Washington, D.C. 20231

Box AF

ASSISTANT COMMISSIONER FOR PATENTS

Washington, D.C. 20231

Sir:

TOTAL

INDEP.

Transmitted herewith is an Amendment in the above-identified application. Also enclosed are two return receipt postcards.

PRESENT

EXTRA

0

1

If any extension of time is needed, then this response should be considered a petition therefor.

HIGHEST NO.

PREVIOUSLY

PAID FOR

** 21

*** 3

The filing fee has been calculated as shown below:

CLAIMS

REMAINING **AFTER**

AMENDMENT

* 21

* 4

SMALL ENTITY

RATE ADDIT. FEE x \$9.00 =x \$39.00 =+ \$130.00 =

TOTAL

RATE	ADDIT. FEE
x \$18.00 =	\$0.00
x \$78.00 =	\$78.00
+ \$260.00 =	

\$78.00

SMALL ENTITY

Please charge Deposit Account No. 20-1430 as follows:

[X]

MINUS

MINUS

[] FIRST PRESENTATION OF MULTIPLE DEP. CLAIM

TOTAL

[X] Any additional fees associated with this paper or during the pendency of this application.

2 extra copies of this sheet are enclosed.

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78.00 CH

TOWNSEND and TOWNSEND and CREW LLP

Chun-Pok Leung Reg. No. 41,405

Attorneys for Applicant

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dence is being deposited with the United I hereby certify that this corresp States Postal Service as first class mail in an envelope addressed to:

EXPEDITED PROCEDURE -

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Assistant Commissioner for Patents

Washington, D.C. 20231

ENT UNDÉR 37 CFR 1.116 **EXAMINING GROUP 1763**

Attorney Docket No.: AM2119/T21300

TTC No.: 16301M-021300

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Karl Littau et al.

Application No.: 08/893,917

Filed: July 11, 1997

For: REMOTE PLASMA CLEANING

SOURCE HAVING REDUCED

REACTIVITY WITH A SUBSTRATE PROCESSING

CHAMBER

Examiner:

Rudy Zervigon

AMENDMENT UNDER 37 CFR 1.116

EXPEDITED PROCEDURE

EXAMINING GROUP 1763

Box AF

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Final Office Action mailed March 10, 2000, and for the purpose of putting the application in condition for allowance, please amend this application as follows. If the amendments are not deemed to put the application in condition for allowance, please enter the amendments to narrow the issues for appeal.

IN THE CLAIMS:

Please amend claims 1, 4, 8, and 16 as follows. Note that the remaining claims are unamended, but are reproduced below for the Examiner's convenience and reference.

(Amended) A method of removing residue from a substrate processing chamber, said method comprising the steps of: